Growth Mechanism and Kinetics of Nb₃Sn in Vapor Diffusion Process

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Outline

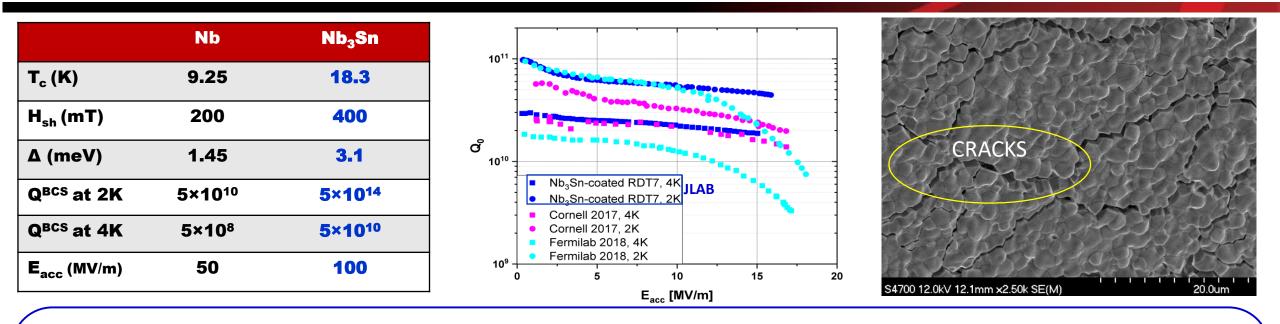
- Nb_3Sn
- Coating growth in vapor diffusion process
 - Nucleation
 - Growth kinetics
- Summary







Nb₃Sn: future SRF cavity material



+ Nb cavities are approaching the intrinsic material limit for the pure material. + Higher T_c and H_{sh} of Nb₃Sn promise **better RF performance** (Q₀ and E_{acc}) and/or **higher operating temperature** (2 K Vs 4.2 K).

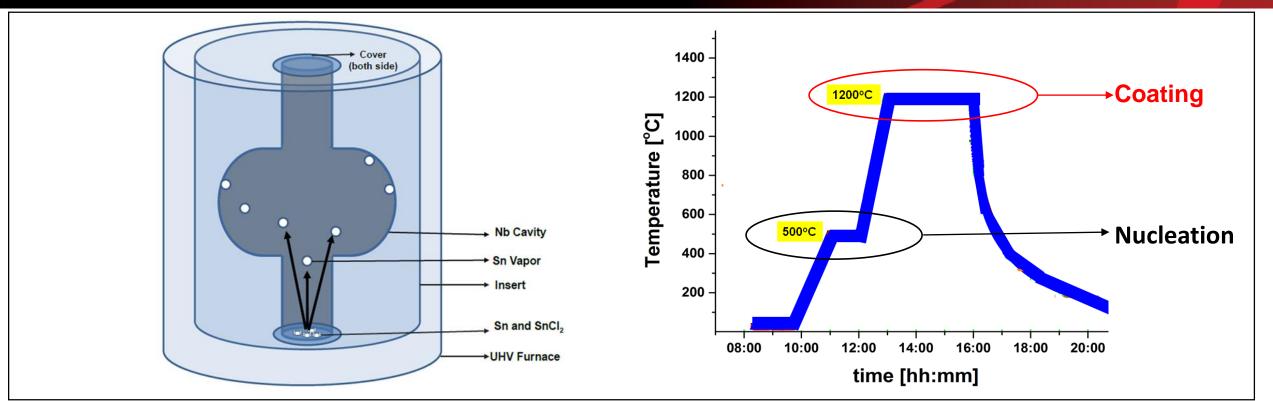
- Extremely brittle material with lower thermal conductivity restricts application into a thin film/coating form.







Vapor diffusion process



Some variations:

- Separate heater for tin source
- Different temperatures profile for substrate and Sn source
- Pre-anodization
- Active/passive pumping

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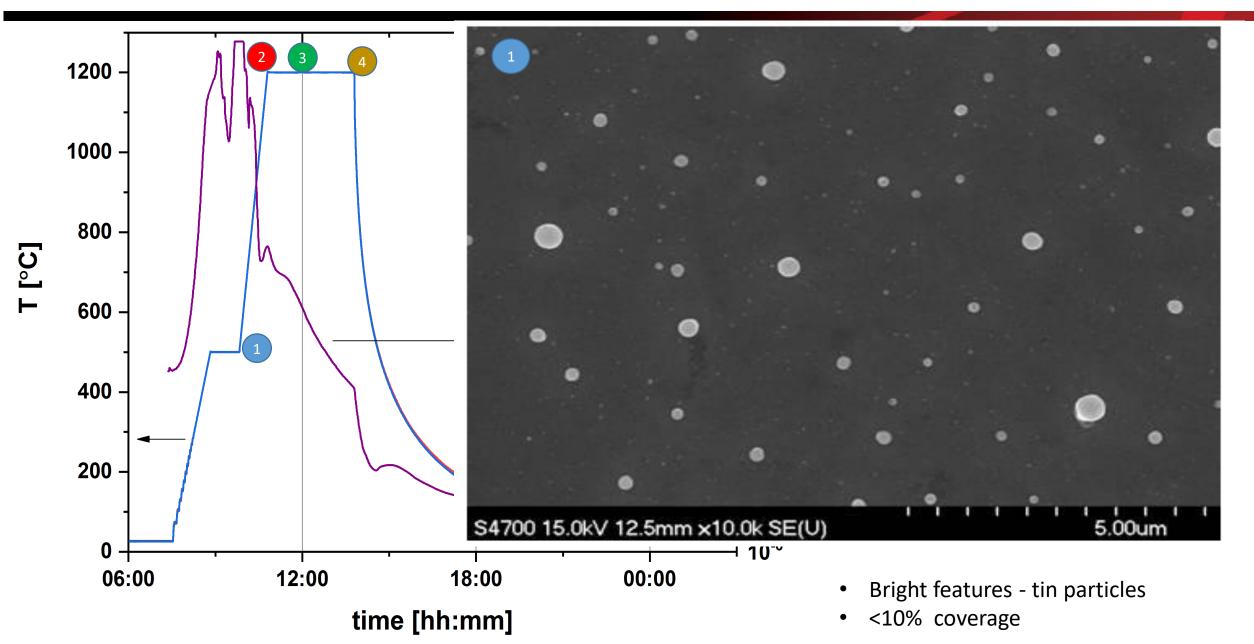




Most successful technique so far to

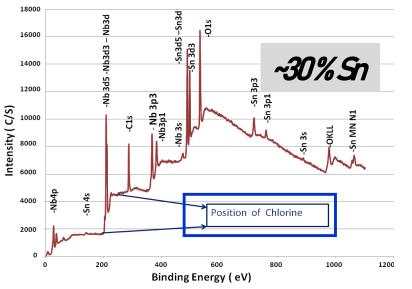
produce promising cavities.

Nb₃Sn coating evolution during vapor diffusion process

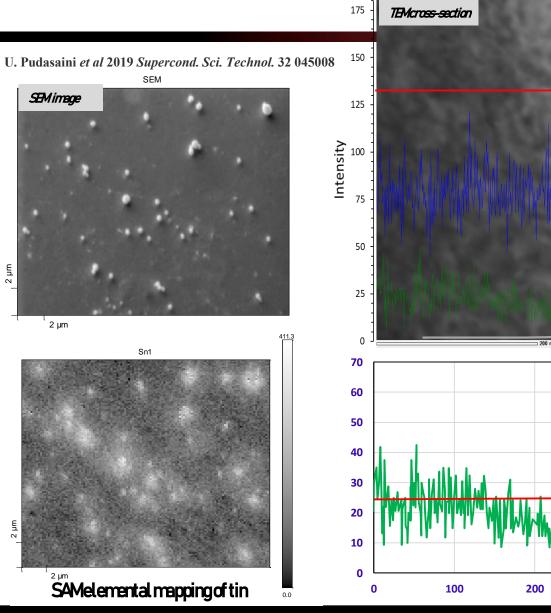


Nucleation

Surface analysis shows ultra-thin tin film of Sn beside Sn particles.



- Significantly lower amount of SnCl₂ also produces similar surface with smaller tin particles.
- Advantageous to have uniform coating.







400 nm

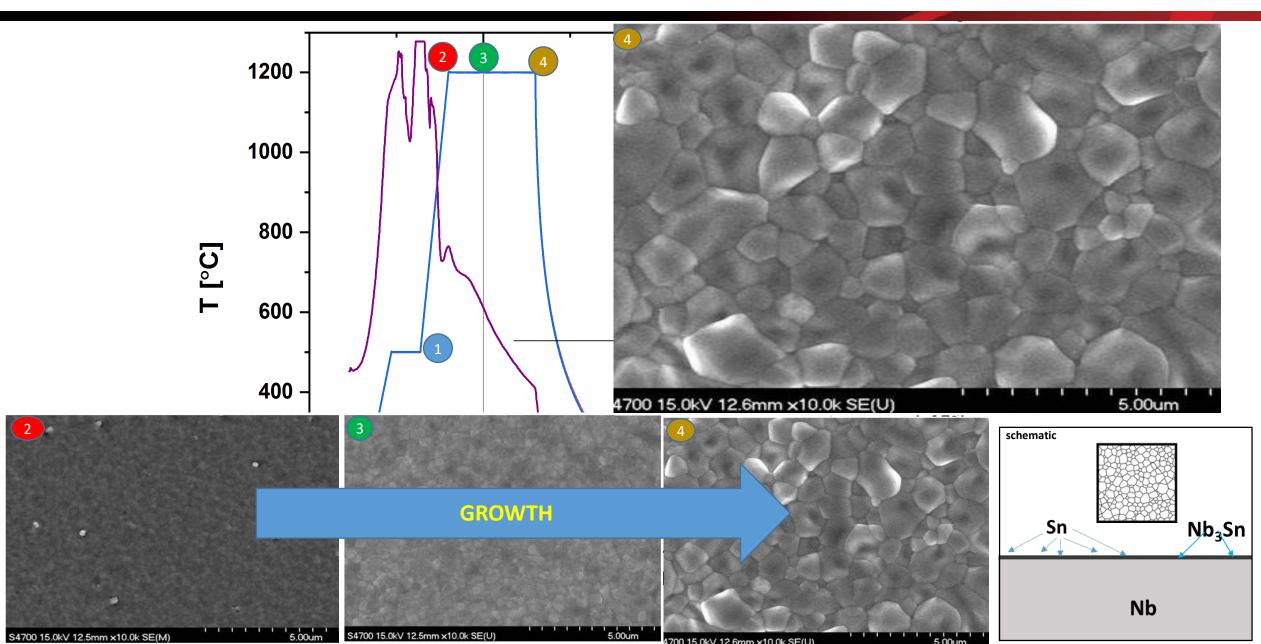
300

OK

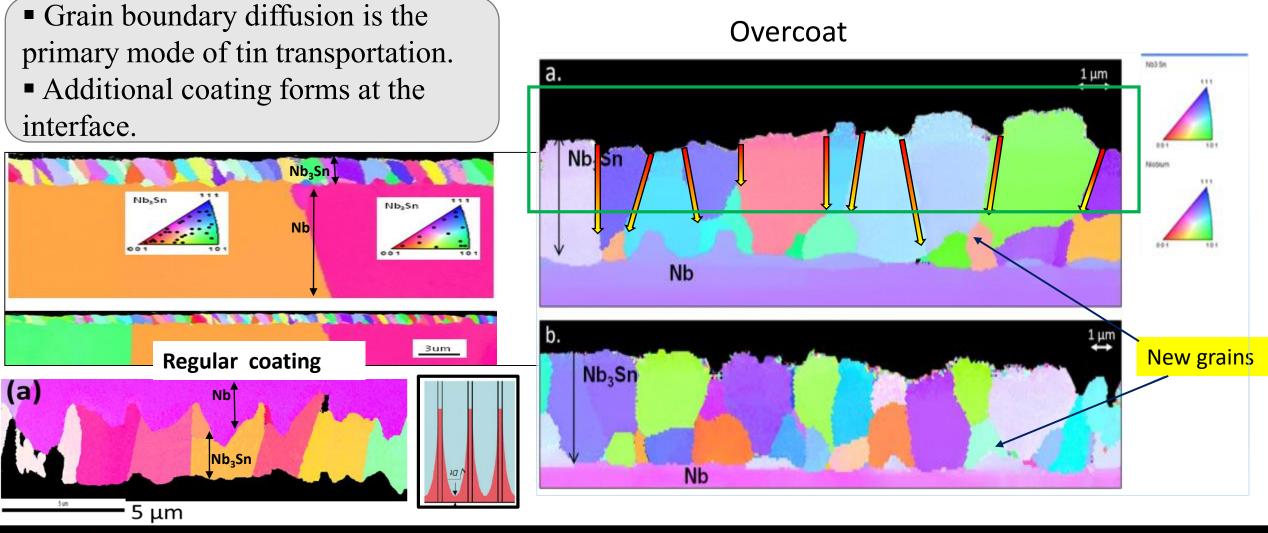
Sn L

Sn

Nb₃Sn coating evolution during vapor diffusion process



Overcoat experiment: grain boundary diffusion

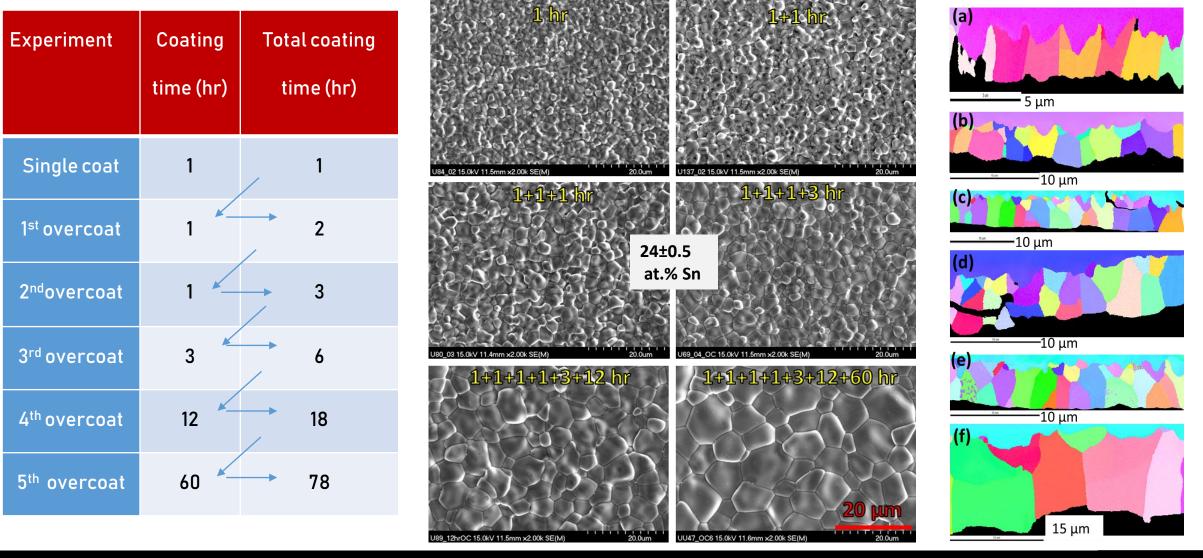








Sequential overcoat experiments

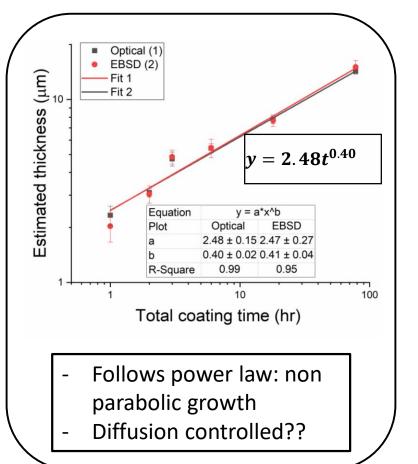


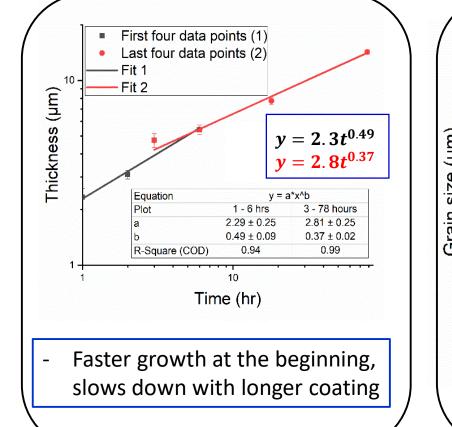
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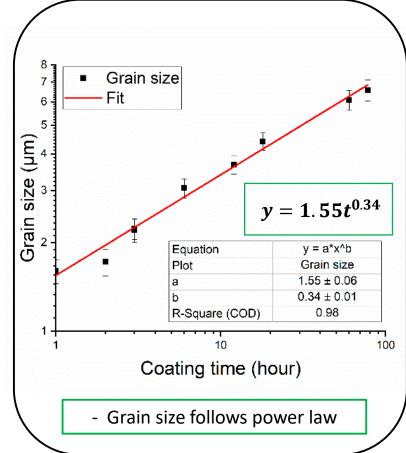




Growth kinetics







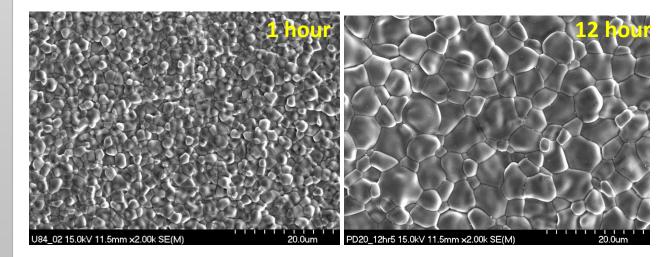






Coating thickness, grain boundary diffusion and grain growth

- Bulk diffusion or fixed array of GB diffusion should show parabolic law (y² ∝ t).
- Why coating thickness does not follow parabolic relation with time?



- Substantial increase in grain size: reduced number of diffusion paths
- Reduced number of diffusion path: depletion of Sn supply at the growth interface reduction in growth rate.
- Longer diffusion path following increased thickness of the coating

$$\mathbf{z} = \boldsymbol{\beta}(T) t^{\mathbf{0.5}(1-m)}$$

Thickness growth exponent

Grain growth exponent

H. H. Farrell, G. H. Gilmer and M. Suenaga, *J. Appl. Phys.*, vol. 45, (9), pp. 4025-4035, 1974.

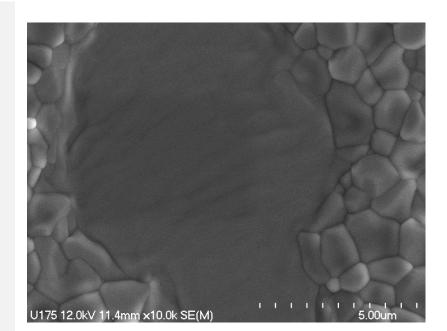




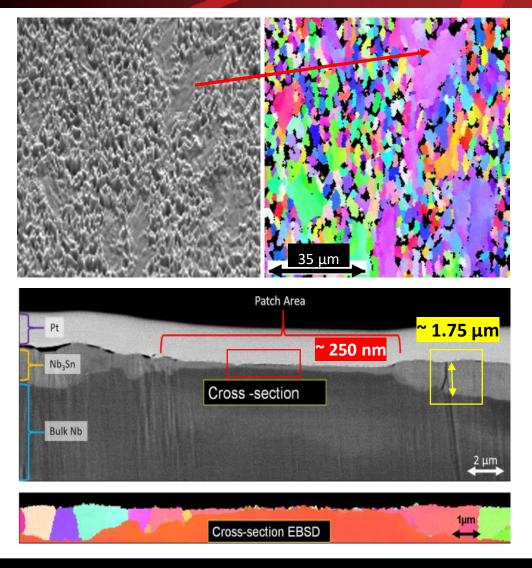


Patchy region

- Consistently reported by several labs
- EDS: Low tin concentration compared to normal coating
- Size: as small as 5 μm to as large as 100 μm
- Cross-section: relatively thin layer
- Potentially affects RF performance



Patchy region has only a few grain boundaries at perimeter for downward diffusion of tin resulting in slowdown of grain growth.









Summary

- **Two-step vapor diffusion** is the technique of choice, producing promising Nb₃Sn cavities.
- <u>3D Tin particle and 2D tin film</u> formation during the nucleation step of the coating is **advantageous** to have the uniform coating.
- Following nucleation, tin evaporates from tin source to form Nb₃Sn layer at the niobium surface. Grain boundary diffusion of tin to the Nb-Nb₃Sn interface defines further growth of the coating.
- Non-parabolic relationship between coating thickness and time $(y^2 \not \prec t)$ is explained by significant grain growth.
- Low density of grain boundaries results in thin coating in patchy regions.







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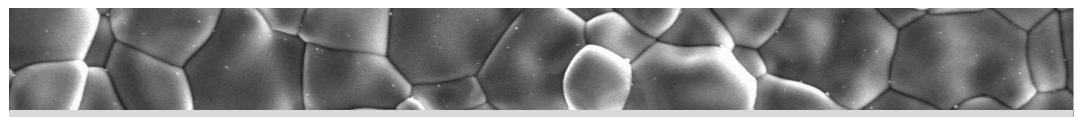
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Thank you for your attention!

